

FORM PTO-1449 (REV. 7-80)      U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE				ATTY. DOCKET NO.	SERIAL NO.		
				TI-36749			
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	BA						
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
SF	CA	"Applied Centura DPS Etch - DPS Plus for Metal Applications", website <a href="http://www.appliedmaterials.com/products/metal_etch_dps_plus_centura.html">http://www.appliedmaterials.com/products/metal_etch_dps_plus_centura.html</a> , printed on 12/4/2003, 1 page.					
	CB	"Applied Centura DPS Etch - DPS II for Metal Applications", website <a href="http://www.appliedmaterials.com/products/metal_etch_dps_ii_centura_300.html">http://www.appliedmaterials.com/products/metal_etch_dps_ii_centura_300.html</a> , printed on 12/4/2003, 1 page.					
	CC	"Applied Centura DPS Etch - DPS Plus for Silicon Applications", website <a href="http://www.appliedmaterials.com/products/silicon_etch_dps_plus.html">http://www.appliedmaterials.com/products/silicon_etch_dps_plus.html</a> , printed on 12/4/2003, 1 page.					
	CD	"Applied Centura DPS Etch - DPS II for Silicon Applications", website <a href="http://www.appliedmaterials.com/products/silicon_etch_dps_ii_300.html">http://www.appliedmaterials.com/products/silicon_etch_dps_ii_300.html</a> , printed on 12/4/2003, 1 page.					
✓	CE	"Applied Centura eMAX Etch", website <a href="http://www.appliedmaterials.com/products/dielectric_etch_emax.html">http://www.appliedmaterials.com/products/dielectric_etch_emax.html</a> , printed on 12/4/2003, 1 page.					
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JF	CA	"Applied Centura Enabler Etch", website <a href="http://www.appliedmaterials.com/products/dielectric_etch_enabler.html">http://www.appliedmaterials.com/products/dielectric_etch_enabler.html</a> , printed on 12/4/2003, 1 page.					
	CB	"Applied Centura EnTek Etch - for Dielectric Applications", website <a href="http://www.appliedmaterials.com/products/dielectric_etch_emax_entek.html">http://www.appliedmaterials.com/products/dielectric_etch_emax_entek.html</a> , printed on 12/4/2003, 1 page.					
	CC	"Applied Producer Etch", website <a href="http://www.appliedmaterials.com/products/producer_etch.html">http://www.appliedmaterials.com/products/producer_etch.html</a> , printed on 12/04/2003, 1 page.					
	CD	"Applied Centura HART Etch for Silicon Applications", website <a href="http://www.appliedmaterials.com/products/silicon_etch_hart.html">http://www.appliedmaterials.com/products/silicon_etch_hart.html</a> , printed on 12/4/2003, 1 page.					
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